

Japan Micropatterning Committee Meeting Summary and Minutes

SEMI Japan Standards Spring 2014 Meetings
Wednesday, April 23, 2014 15:30-17:00
SEMI Japan, Tokyo, Japan

Next Committee Meeting

SEMI Japan Standards Spring 2014 Meetings
Wednesday, October 8, 2014, 15:30-17:00
SEMI Japan, Tokyo, Japan

Table 1 Meeting Attendees

Co-Chairs: Morihisa Hoga (Dai Nippon Printing)

SEMI Staff: Naoko Tejima (SEMI Japan)

<i>Company</i>	<i>Last</i>	<i>First</i>	<i>Company</i>	<i>Last</i>	<i>First</i>
Dai Nippon Printing	Hoga	Morihisa	Dai Nippon Printing	Suzuki	Toshio
-	Otaki	Masao	SEMI Japan	Tejima	Naoko

** alphabetical order by last name*

Table 2 Leadership Changes

None

Table 3 Ballot Results

None

Table 4 Authorized Activities

None

Table 5 New Action Items

<i>Item #</i>	<i>Assigned to</i>	<i>Details</i>
MP120828-2	5 Year Review Task Force	To draft the document of Doc. 5484, Revision to SEMI P22-0307 to submit it for the earliest possible cycle.
MP121211-1	5 Year Review Task Force	To draft the document of Doc. 5537, Line Item Revision to SEMI P23-0200 to submit it for the earliest possible cycle.
MP130828-1	5 Year Review Task Force	To draft the background statements for the Document #5484 and #5537
MP140423-1	Mask Data Format for Mask Tools Task Force	To submit Doc. #5229, Revision to SEMI P44-0211, Specification for Open Artwork System Interchange Standard (OASIS) Specific to Mask Tools, for cycle 5, 2014.

1 Welcome, Reminders and Introductions

Morihisa Hoga, committee co-chair, called the meeting to order at 15:30. Self-introductions were made followed by the agenda review.

2 Required Meeting Elements

The meeting reminders on program membership requirement, antitrust issues, intellectual property issues and international effective meeting guidelines, were reviewed by SEMI staff, Naoko Tejima.

3 Review of Previous Meeting Minutes

The committee reviewed the minutes of the previous meeting held on December 11, 2013.

Motion: To approve the minutes of the previous meeting as submitted.

By / 2nd: Masako Otaki (-) / Toshio Suzuki (Dainippon Printing)

Discussion: None

Vote: 2 in favor and 0 opposed. **Motion passed.**

Attachment: 01_JA_Micropatterning_Previous_Mtg_Minutes_140423

4 SEMI Staff Report

Naoko Tejima gave the SEMI staff report. This report included SEMI Global 2014 Calendar of Events, Global Standards Meeting Schedule, 2014 Critical Dates for SEMI Standards Ballots, SEMI Standards Publication, A&R Ballot Review Report and Contact Information.

Attachment: 02_SEMI_Staff_Report_140423

5 Liaison Reports

5.1 North America Microlithography Committee Report

No report was provided. Because the NA Committee meeting has not been held since it was held at the SEMICON West in July, and the next meeting will be held at SEMICON West 2014.

6 Task Force Reports

6.1 Mask Data Format for Mask Tools Task Force

Toshio Suzuki reported for the Mask data Format for Mask Tools Task Force. Of note:

- Task Force is working for the below 2 documents.
 - Doc.5229, Revision to SEMI P44-0211, Specification for Open Artwork System Interchange Standard (OASIS) Specific to Mask Tools.
 - Doc.4840, Revision to SEMI P45-0708, Specification for Job Deck Data Format for Mask Tools Type of Document: Revision to an existing Standard/Guideline
- Document 5229 will be submitted for cycle 5.

Action Item: Mask Data Format for Mask Tools Task Force to submit Doc. #5229 for cycle 5, 2014.

6.2 5 Year Review Task Force

Masao Otaki reported on progress for the 5 Year Review Task Force. Of note:

- Task Force is drafting the below 2 documents and they are planning to submit the letter ballot for the earliest possible cycle.
 - Doc.5484, “Revision to SEMI P22-0307, Guideline for Photomask Defect Classification and Size Definition”.
 - Doc.5537, “Line Item Revision to SEMI P23-0200 (Reapproved 1107), Guidelines for Programmed Defect Masks and Benchmark Procedures for Sensitivity Analysis of Mask Defect Inspection Systems”

7 Old Business

7.1 Previous Meeting Action Items

Naoko Tejima reviewed the previous meeting action items.

Table 6 Previous Meeting Actions Items

<i>Item #</i>	<i>Assigned to</i>	<i>Details</i>
MP120828-1	Mask Data Format for Mask Tools Task Force	To prepare the information (blue) ballot of Doc. 5229, Revision to SEMI P44 for Cycle 5, 2014. ... Close
MP120828-2	5 Year Review Task Force	To draft the document of Doc. 5484, Revision to SEMI P22-0307 to submit it for the earliest possible cycle. ... Open
MP121211-1	5 Year Review Task Force	To draft the document of Doc. 5537, Line Item Revision to SEMI P23-0200 to submit it for the earliest possible cycle. ... Open
MP130828-1	5 Year Review Task Force	To draft the background statements for the Document #5484 and #5537. ... Open
MP131211-1	Toshio Suzuki	To have the TF meeting in January. ... Close

8 New Business

None

9 Action Item Review

9.1 New Action Items

Naoko Tejima reviewed the new action items. These can be found in the New Action Items table at the beginning of these minutes.

10 Next Meeting and Adjournment

The next meeting of the Japan Micropatterning Committee is scheduled for Wednesday, October 8, 2014, 15:30-17:00, at SEMI Japan, Tokyo, Japan.



Respectfully submitted by:
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Minutes approved by:

Morihisa Hoga (Dai Nippon Printing), Co-chair	August **, 2014
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Table 7 Index of Available Attachments #1

#	<i>Title</i>
1	JA_Micropatterning_Previous_Mtg_Minutes_140423
2	SEMI_Staff_Report_140423

#1 Due to file size and delivery issues, attachments must be downloaded separately. A .zip file containing all attachments for these minutes is available at www.semi.org. For additional information or to obtain individual attachments, please contact Naoko Tejima at the contact information above.